Radiation Hardness CMS HGCal Silicon Sensors



16th Terascale Detector Workshop

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Globally

- New endcap calorimeter for CMS ($|\eta| = 1.5 3$)
- 620 m² Si, 6M channels

Si sensors:

- High fluences up to 10^16 neq/cm2
- Two different sensor types, different optimal annealing scenarios
- Large area to cover with Si sensors: production line for 8" wafers being commissioned for HGCAL
- Radiation damage and annealing behaviour needs to be understood
- Crucial input for operation and warming up scenarios during technical stops

The HGCAL







The Breadth of Studies



- In general three thicknesses and technologies
- → 300µm (FZ), up to 2 * 10¹⁵ n_{eq}/cm²
- ▶ 200µm (FZ), up to 5 * 10¹⁵ n_{eq}/cm²
- ▶ 120µm (EPI), up to 10 * 10¹⁵ n_{eq}/cm²

Assuming 3 ab⁻¹

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Surface



Bulk material







Full Sensor Studies





- Handling and 'physical robustness'
- HV stability, radiation hardness
- Homogeneity of cell properties
- Impact of geometry: partials, edges, supply lines, ...









Irradiation of large wafers at RINSC





In a cylinder with dry ice

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• Fluences up to 1 (1.6) n_{eq}/cm^2 expected for 3 (4.5) ab⁻¹ of data

- Long exposure in the reactor
- Substantial annealing during irradiation
- Constant temperature monitoring required
- Recently achieved to stay within beneficial annealing regime
 - Optimised puck material
 - Split irradiation rounds





The Probe Station





- Temperature controlled chuck ranging from -40°C to typical annealing temperatures
- Open source design of probe card

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E. Brondolin, et al, arXiv:1903.10262, NIM A







2.4

Values for U = 600.0 V





Values for U = 600.0 V

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full

Full and Partial Sensor Leakage Current



°_

7.5 °₽

6.5

Values for U = 600.0 V

- Volume-normalised current increases with fluence
- Global pattern similar for all sensors in an irradiation batch
- Fluence or annealing time profiles

• Locally, all cells, including those in proximity to dicing and internal supply lines, show very consistent leakage current behaviour









Quantitative Overview





Outer Calibration cell (#29)

Edge Large cell (#192)

700

800

 $U_{bias}(V)$

500

600



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- Select cells on isofluence lines
- Normalise each cell current to the cell volume: ρ_I
- Normalise to the standard cell ρ
- Agree within 10% for different cell layouts and positions
- Mostly constant with bias voltage (same scaling)
- Even for large wafers, and partial wafers, the electrical characteristics are mostly homogenous

CMS HGCAL Collaboration, arXiv:2209.10159, JINST O. Kaluzinska, https://indico.cern.ch/event/1334364/contributions/5672066/







- EM radiation (X-ray) creates electron-hole pairs in the SiO₂ layer
- Holes can be trapped
- Creates charge build-up at the interface
 - Can deteriorate inter-pad isolation
- $N \propto V_{FB}$



[PhD thesis of Ioannis Kopsalis]

- Anneals relatively fast
- Challenging to measure in a reproducible way

Surface Damage



[Illustration V. Hinger]







X-ray Irradiation of Test Structure



- Sample cooled during irradiation and measurement
- Integrated setup avoids moving the sample between irradiation and measurement steps
- Fully automated measurement software enables reproducible and long term measurements
- Allows systematically studying of different oxide variants provided by the manufacturer





Oxide Quality



- Long continuous measurement campaigns possible (10² kGy correspond to a week)
- Detailed study of oxide quality using a floating and biased MOS (to emulate an electric field) ... and other properties
- "New Type C" chosen for production

M. Defranchis,

https://indico.cern.ch/event/1096847/contributions/4743792/ paper in preparation



Characterising the Bulk Material



- Combined setup to measure charge collection, leakage current, and capacitance
- Enables precise and long-term annealing studies
- Irradiation of samples: JSI (well controlled environment)

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Electrical Characteristics



- The electrical capacitance can provide a handle to extract the depletion voltage
- Beneficial annealing dominates until approx. 100 minutes @ 60°C



J.K. et al, arXiv:2211.04849, JINST

e depletion voltage 60°C









- Depletion voltage extracted from capacitance measurements depends on measurement frequency
- Higher fluencies and thicker sensors increase frequency dependence: there is no "good" frequency
- Frequency dependence also depends on annealing
- Investigate collected charge instead

Frequency Dependence

J.K. et al, arXiv:2211.04849, JINST L. Diehl, https://indico.cern.ch/event/1270076/contributions/5450197/









Charge Collection Efficiency Annealing





- A broad program of measurements to study the radiation hardness of the HGCAL silicon
 - Full sensors
 - Surface effects
 - Bulk properties
- First measurements with full and partial sensors up to $1.4 \ 10^{16} \, n_{eq}/cm^2$
- Qualified surface damage in a reproducible manner
- Comprehensive studies of the bulk material in terms of electrical characteristics and charge collection also extending to different annealing temperatures

Summary







BACKUP

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CCE measurement



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Full Sensor Irradiation Cooling





Dry ice for cooling of the cylinder



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Cylinder in reactor beam port radial to reactor core







Wafer Types

Low-Density sensor ~ 200 cells of 1.1 cm² size 300 µm & 200 µm active thickness



High-Density sensor ~ 450 cells of 0.5 cm² size

120 µm active thickness



Low-Density "Partial sensor" example from "Multi-Geometry" sensor



High-Density "Partial sensor" example from "Multi-Geometry" sensor



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